

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION of :

Takeshi MORITA :

Serial No. [NEW] :

Filed: July 28, 2003 :

Method for Estimating Remaining Film Thickness Distribution, Method for Designing Patterning Mask Using the Method for Estimating Remaining Film Thickness Distribution, and Method for Manufacturing Semiconductor Devices by Using Patterning Mask Designed by Using the Method for Estimating Remaining Film Thickness Distribution

PRELIMINARY AMENDMENT

U.S. Patent and Trademark Office
2011 South Clark Place
Customer Window, **Mail Stop Patent Application**
Crystal Plaza Two, Lobby, Room 1B03
Arlington, VA 22202

Sir:

Preliminary to the examination of the above-identified application,
please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which
begins of page 2 of this paper.

Remarks begin on page 7 of this paper.